

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Docket No: Q96063

Takayuki ARAKI, et al.

Appln. No.: 10/589,504

Group Art Unit: 1752

Confirmation No.: 9430

Examiner: Anca EOFF

Filed: August 15, 2006

For: LAMINATED RESIST USED FOR IMMERSION LITHOGRAPHY

RESPONSE TO RESTRICTION REQUIREMENT

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Responsive to the outstanding Restriction Requirement of August 19, 2008, Applicant elects Group II, claims 8-10 (drawn to a laminated resist in which a photoresist layer is formed on a substrate as an outermost surface of the laminated resist, said photoresist comprising a fluorine-containing polymer with a protecting group which can be converted to an alkali soluble group by an acid and a photoacid generator), for prosecution, without traverse.

Applicant reserves the right to file a Divisional Application directed to the non-elected subject matter.

The USPTO is directed and authorized to charge all required fees, except for the Issue Fee and the Publication Fee, to Deposit Account No. 19-4880. Please also credit any overpayments to said Deposit Account.

Respectfully submitted,



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CUSTOMER NUMBER

Date: September 18, 2008